

Preface

This second issue on the use of chemical vapour routes (CVD) to make thin films follows five years after the first issue. In this time there have been tremendous changes in the field, driven by the utility of CVD, in its myriad aspects. CVD methods of making thin films remain the most successful industrial application of organometallic chemistry today in terms of dollar amounts of final product. As we stated in the first issue, the electronics and optoelectronics industries are based on information processing and storage devices that incorporate a wide variety of thin films that offer conducting, insulating, protective, magnetic, ferroelectric, opti-

cally nonlinear, etc. properties. CVD methods provide some of the very best ways to put down the purest (or selectively doped) films with nearly optimal control of thickness, morphology and properties, during device manufacture. A whole separate field of organometallic chemistry has arisen. In this edition, we highlight several rapidly developing areas of thin film processing some new, some old methods with new materials. The attempt is to give the reader a broad image of the field.

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